| | Hits | Search Text | DBs |
|----|------|---|---|
| 68 | 10 | expos\$4)) and ((photoresist or resist) same pattern) and (ozone | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |
| 69 | 0 | expos\$4) same voltage) and ((photoresist or resist) same | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |
| 70 | 50 | ((ion near9 beam) same (ash\$4 or harden\$4 or (sputter\$4 near16 beam) or (sputter near9 etch\$4)) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |
| 71 | 745 | (((ion near9 beam) or ion) same (ash\$4 or harden\$4 or (sputter\$4 near16 beam) or (sputter near9 etch\$4) or imping\$4 or irradiat\$4 | EPO; JPO; DERWENT; IBM_TDB |

| | Hits | Search Text | DBs |
|----|------|--|---|
| 72 | 695 | S75 NOT S74 | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |
| 73 | 11 | same pattern same ((etch near4 resist\$5) or harden\$5 or cured) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |
| 74 | 7 | BARC or (organic near9 BARC) or | USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |